

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L21	8204	STI or "shallow trench isolation"	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 09:57
L22	26109	"chemical mechanical polishing" or (chemical adj mechanical adj polishing)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 09:58
L23	40705	(mask\$3 or pattern\$4) same (trenches or grooves)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 09:59
L24	7237	(mask\$3 or pattern\$4) same (trenches or grooves) same (resist or photoresist)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 10:50
L25	2532	21 and 22	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 10:00
L26	450	25 and 24	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 10:50
L31	764	(mask\$3 or pattern\$4) same (trenches or grooves) same (resist or photoresist) same polish\$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 10:51
L32	173	31 and 21	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 11:10
L33	0	hoolatz-mark.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 11:10
L34	12	hollatz-mark.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 11:11
L37	19	morhard-klaus-dieter.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 11:12
L38	1	truby-alexander.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/16 11:13